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Optical and electrical properties of $\text{GaAs}_{1-x}\text{Bi}_x/\text{GaAs}$ diodes

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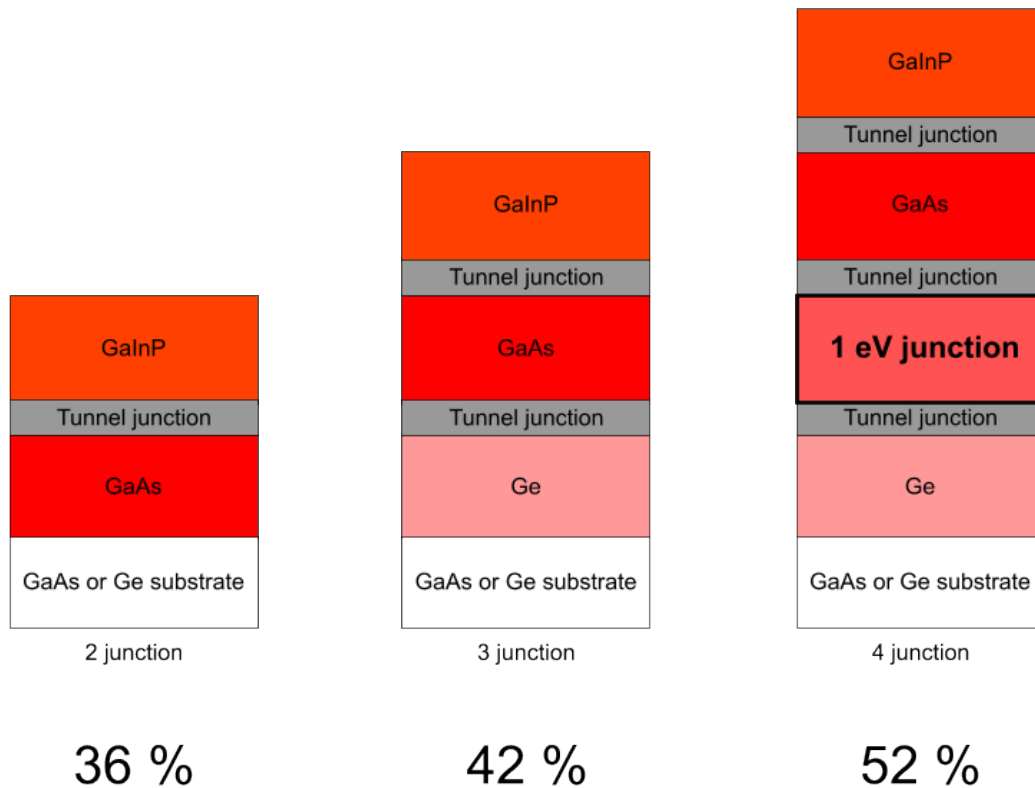
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Outline

- Introduction
- Results
- Future work
- Summary

Multi-junction solar cells: the need for a 1 eV band gap material



Predicted efficiencies under AM1.5D spectrum, 500 suns concentration.

Figures adapted from Friedmann et al., [http://dx.doi.org/10.1016/S0022-0248\(98\)00561-2](http://dx.doi.org/10.1016/S0022-0248(98)00561-2)

InGaAsN

- InGaAsN has been used as a 1eV junction by Solar Century to make a 43.5% efficient MJ solar cell
- However incorporation of N is problematic
- Using N leads to problems such as short diffusion lengths and low depletion widths
- Believed to be caused by defects such as N-N interstitial pairs

GaAsBiN?

- Growth reported by Huang et al. and Tixier et al.
- Huang et al. determined that GaAsBiN is lattice matched to GaAs for the composition $\text{Ga}(\text{N}_{0.33}\text{Bi}_{0.67})_z\text{As}_{1-z}$
- A 1eV band gap is obtained for $z = 0.042$, which corresponds to $x_{\text{N}} = 0.014$ and $x_{\text{Bi}} = 0.028$
- Important to note that N content is **lower** than for InGaAsN with the same band gap ($x_{\text{N}} \sim 0.03$)
- Reducing N content will improve material quality, however need to determine effect of using Bi instead of In

GaAsBi with a 1 eV band gap

- No nitrogen source at present therefore looking at just Bi initially
- GaAs p-i-n diode structures containing undoped GaAsBi layers
- Bi content is expected to be around 6%, giving a band gap around 1 eV
- 4 samples with GaAsBi layers, with thicknesses ranging from 50 nm to 350 nm



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Samples grown using MBE- STM system

MBE
chamber



STM chamber

Sample structure

Material	Type	Doping (cm ⁻³)	Thickness (nm)
GaAs cap	p ⁺	8×10 ¹⁸	600
GaAs spacer	i	N/A	Varied between samples
GaAsBi			
GaAs spacer			
GaAs buffer	n	1×10 ¹⁸	250
GaAs substrate	n ⁺	4×10 ¹⁸	---

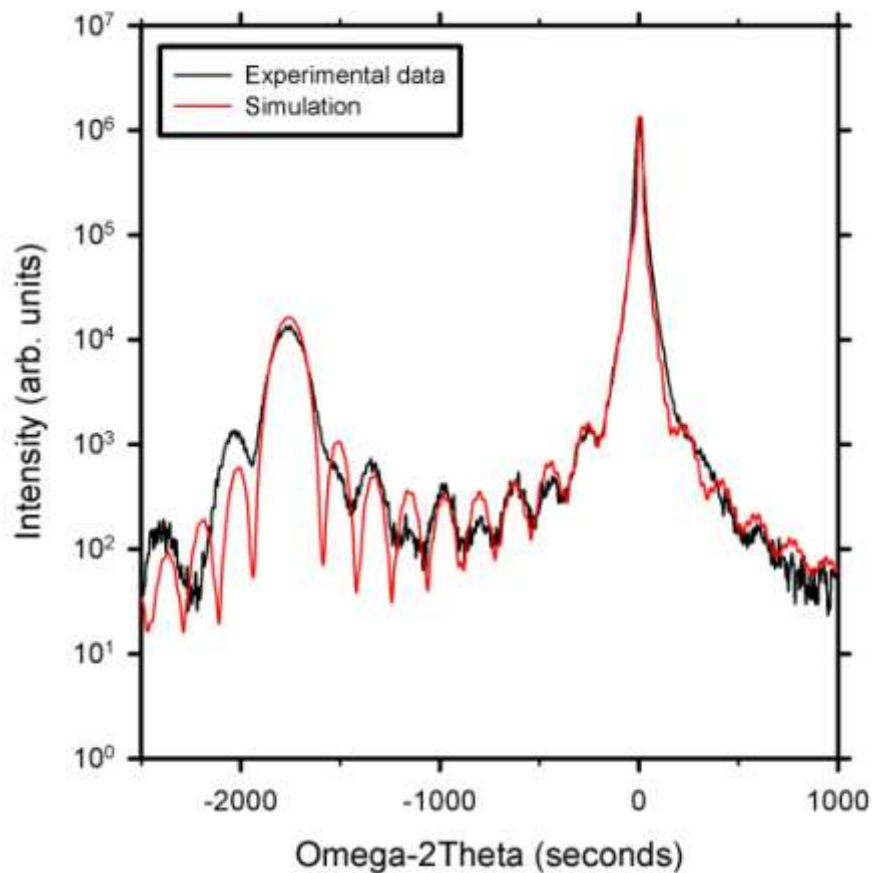
Sample structure

Sample	GaAsBi layer thickness (nm)	GaAs spacer thickness (nm)
B	50	25
C	100	16
D	200	10
E	350	10

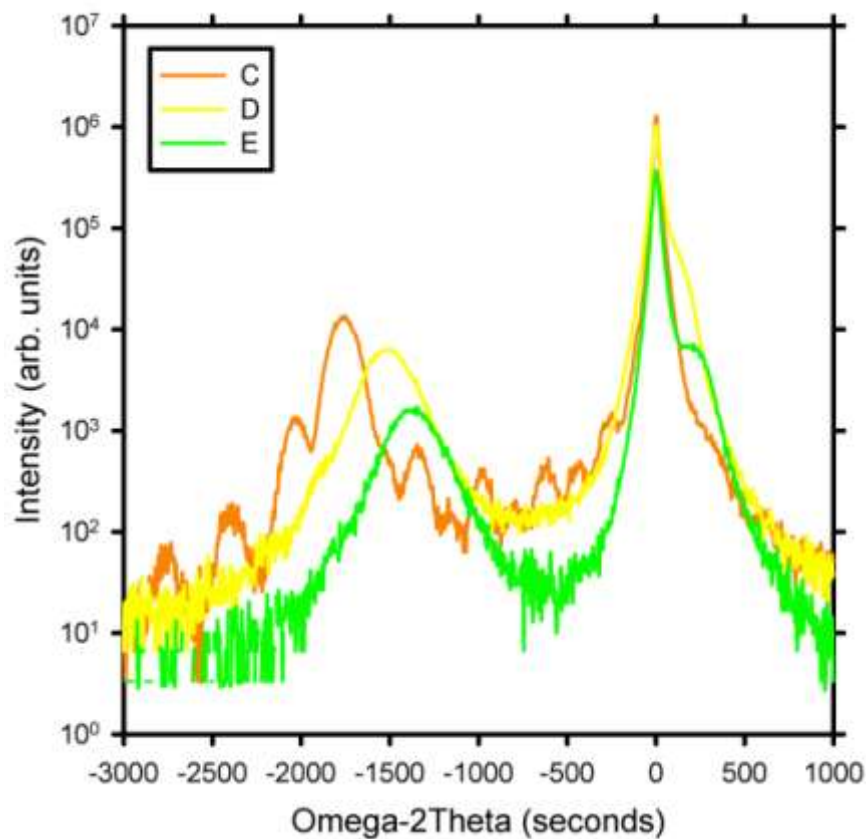
Also grew GaAs control sample "A", with 400 nm i-region

X-ray diffraction

Sample C (100 nm GaAsBi layer)

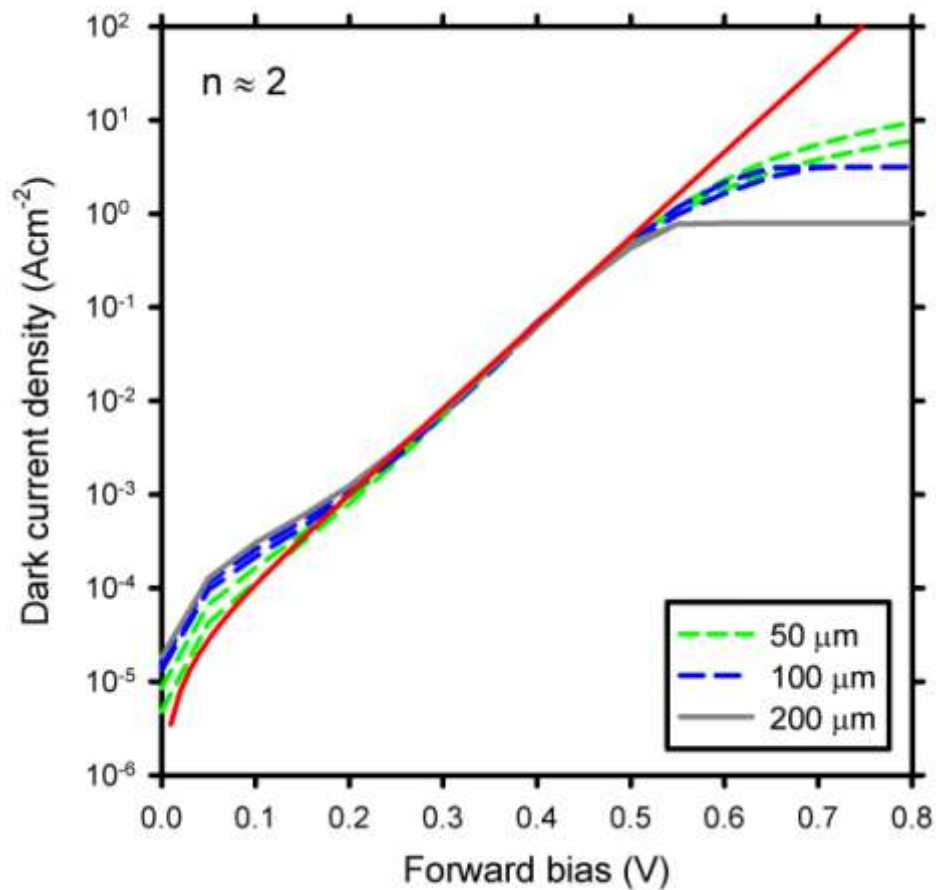


X-ray diffraction



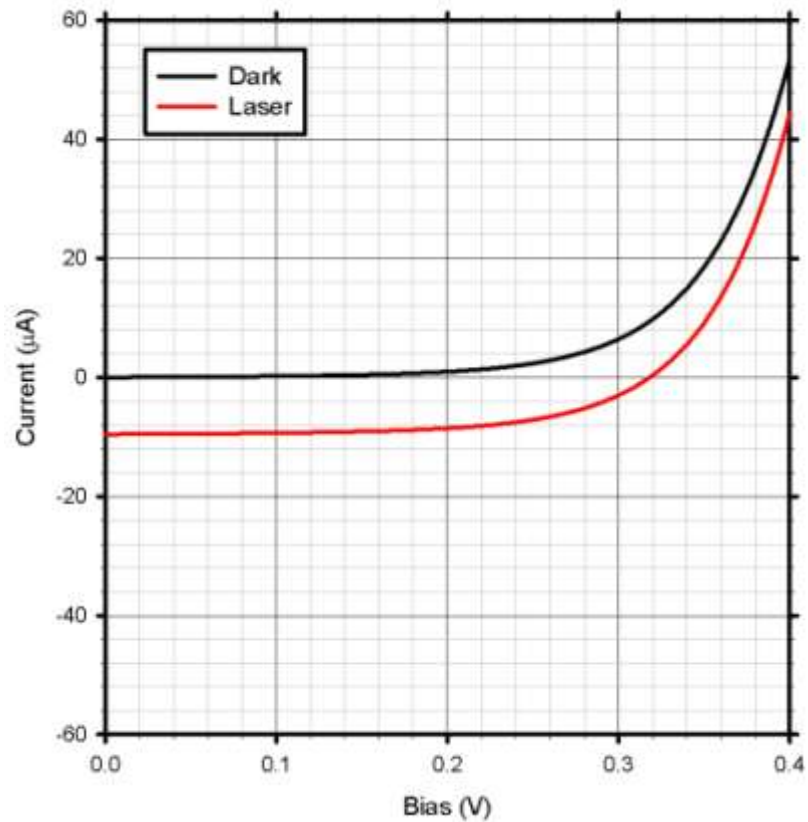
Forward dark J-V

B (50 nm GaAsBi layer)

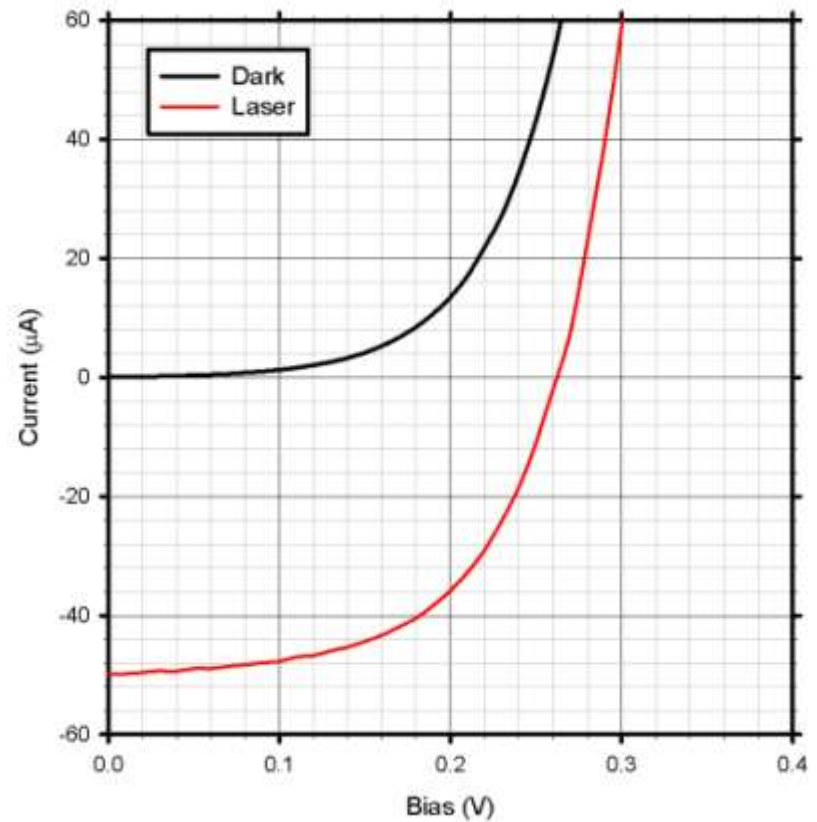


I-V under illumination

B (50 nm GaAsBi layer)



E (350 nm GaAsBi layer)



I-V under illumination

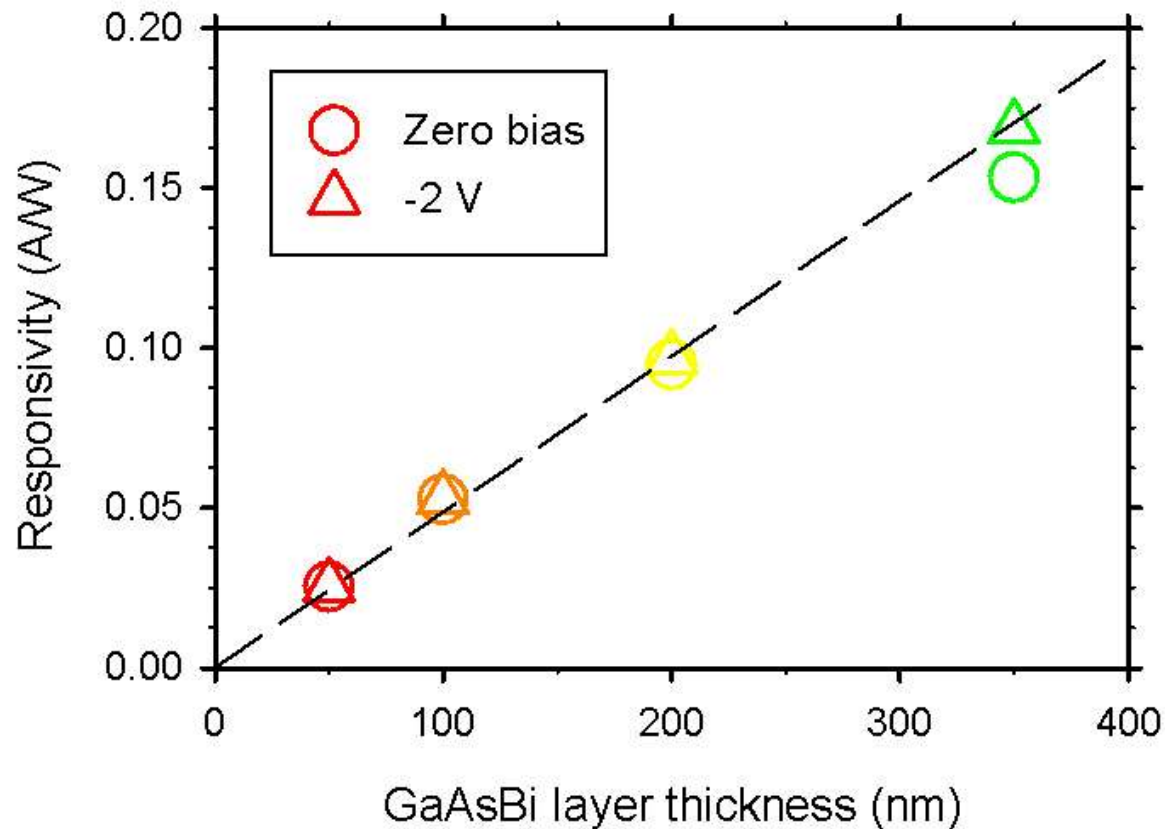
$$V_{oc} \approx \frac{nkT}{q} \ln \left(\frac{J_L}{J_0} \right)$$

J_L increases due to increased absorption

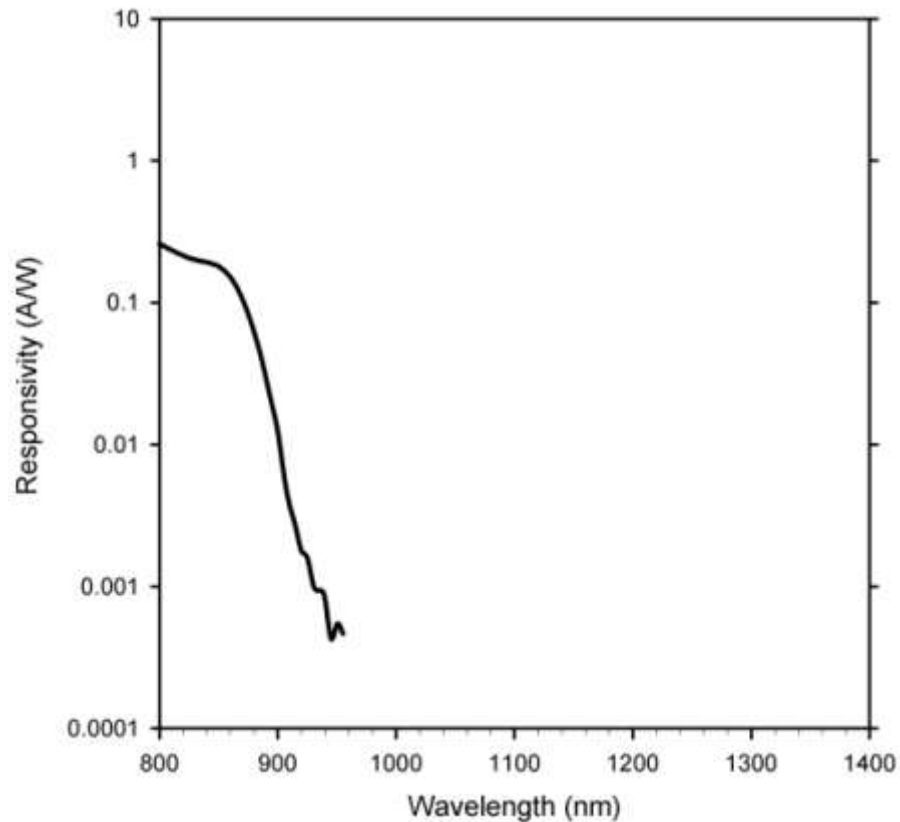
J_0 increases due to greater number of dislocations

Greater increase of J_0 compared to J_L gives decrease in V_{oc}

Responsivity at 1064 nm

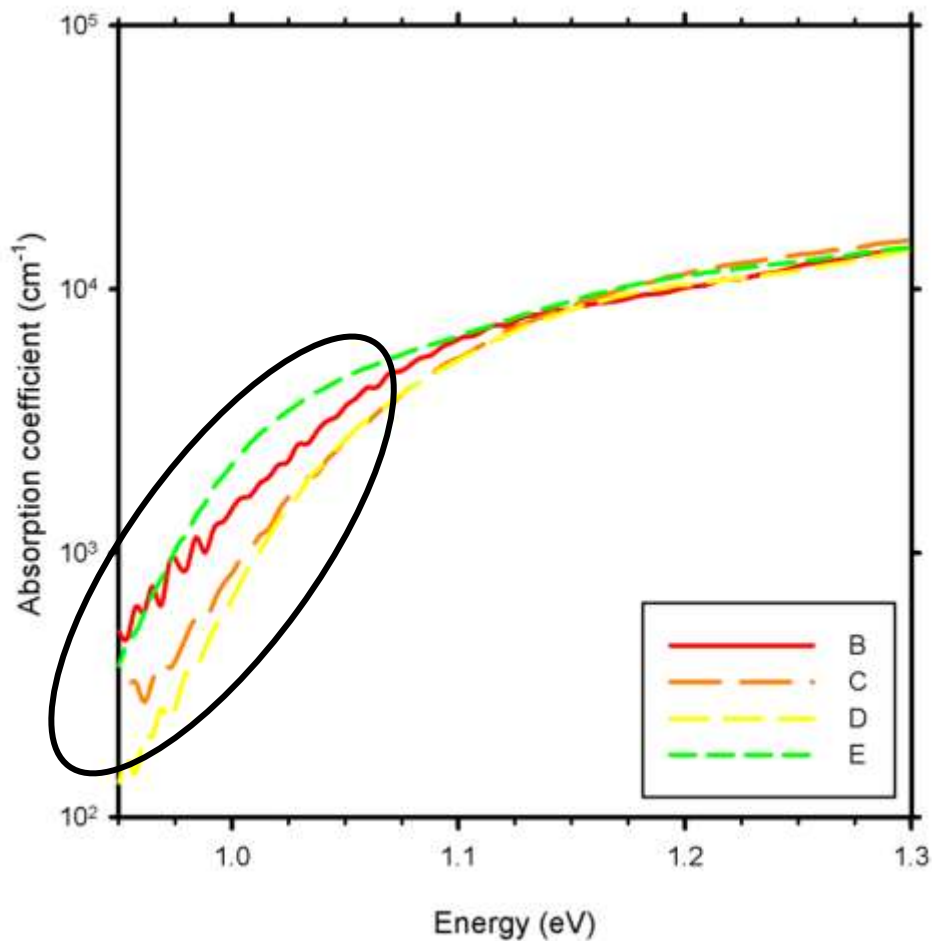


Responsivity as a function of wavelength



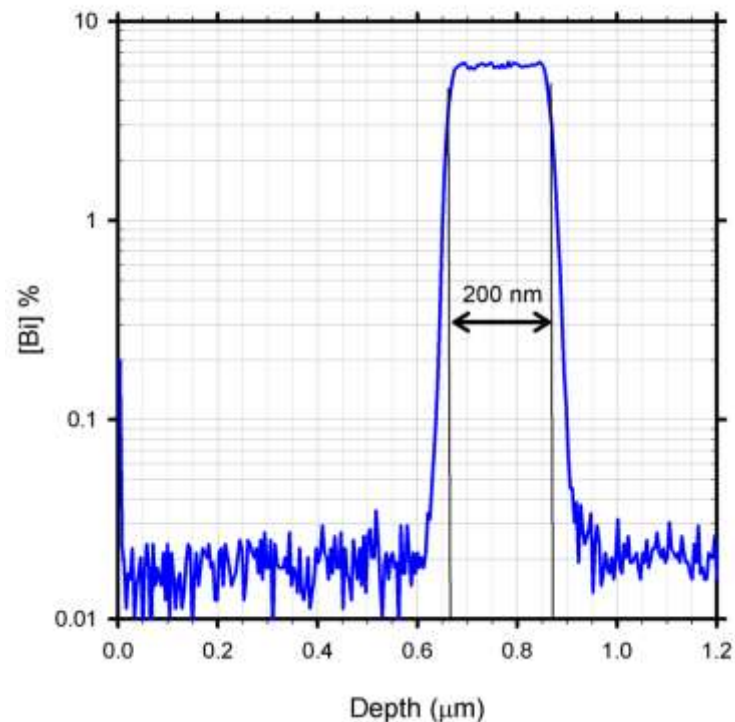
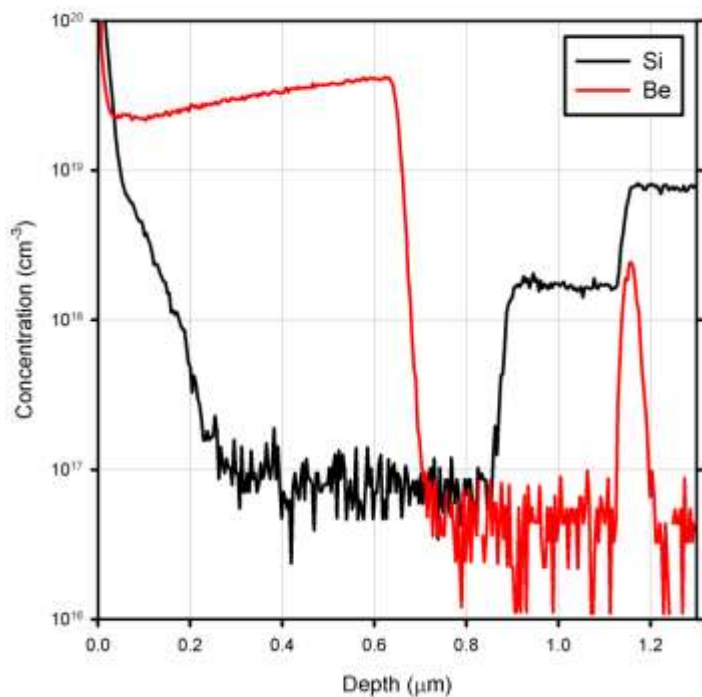
Absorption coefficient

Urbach region



SIMS

Sample D (200 nm GaAsBi layer)



Be concentration higher than expected – non-substitutional Be?
GaAsBi layer thickness roughly as expected
No large variation in Bi content observed

Future work

- Need to investigate effect GaAsBi has on dark currents
- More structural measurements e.g. SIMS, TEM
- Eventually need to consider lattice matching to GaAs, possibly with addition of N to give GaAsN₂Bi

Summary

- GaAsBi/GaAs p-i-n diodes have been grown and fabricated
- The presence of the GaAsBi layer extends the photoresponse into the near-IR
- GaAsBi shows increased absorption below the band gap compared to GaAs

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Questions?